

EEE-2103: Electronic Devices and Circuits

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Field Effect Transistors

FET vs BJT:

FET and BJT are three-terminal devices.

BJT is current-controlled device.

JFET is voltage-controlled device.

BJT \rightarrow *npn* and *pnp*.

JFET \rightarrow *n*-channel and *p*-channel.

BJT \rightarrow bipolar device = conduction level is function of two charge carriers.

FET \rightarrow unipolar device = electron (*n*-channel) or hole (*p*-channel) conduction.

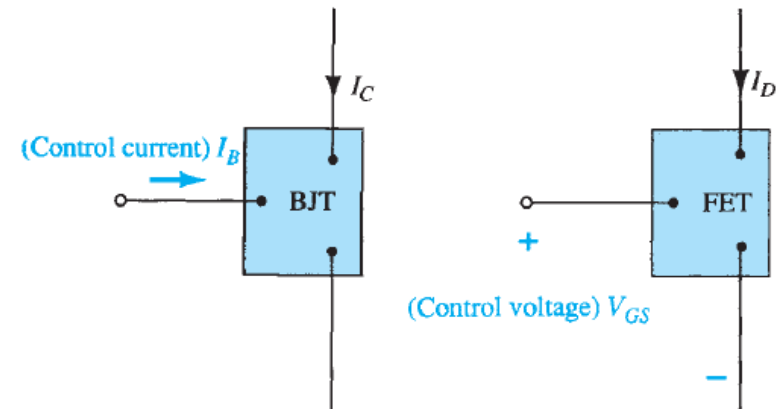
Input impedance \rightarrow FET \gg BJT.

Sensitivity to changes in applied signal \rightarrow BJT \gg FET.

AC voltage gain \rightarrow BJT \gg FET.

Temperature stability \rightarrow FET \gg BJT.

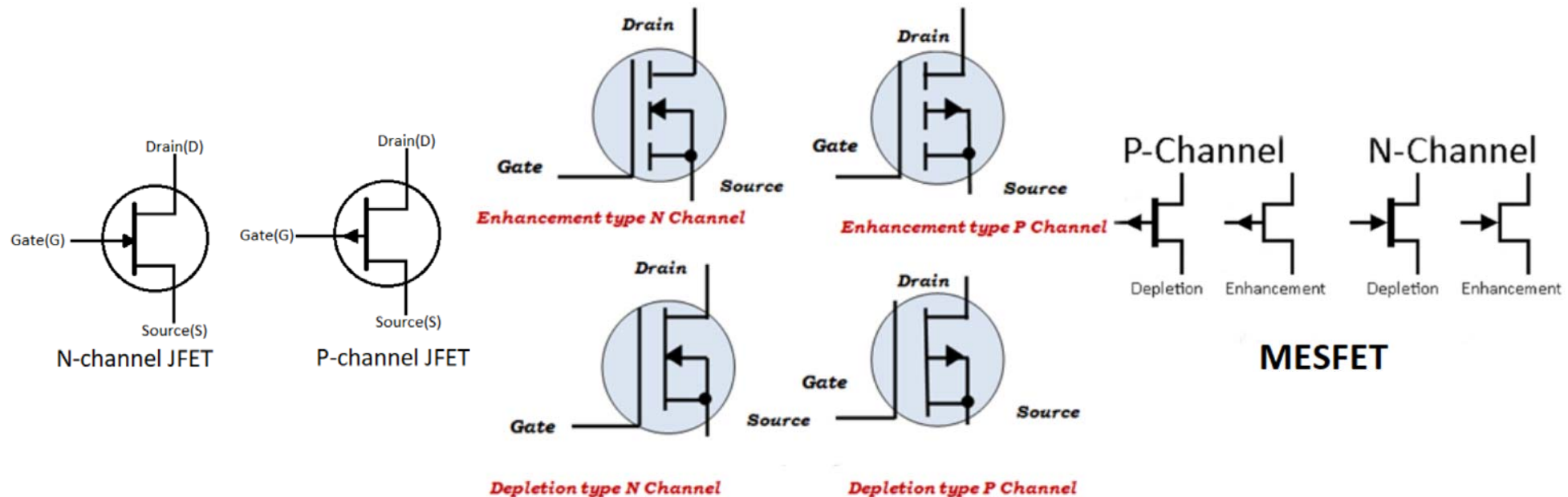
Size \rightarrow BJT \gg FET.



Field Effect Transistors

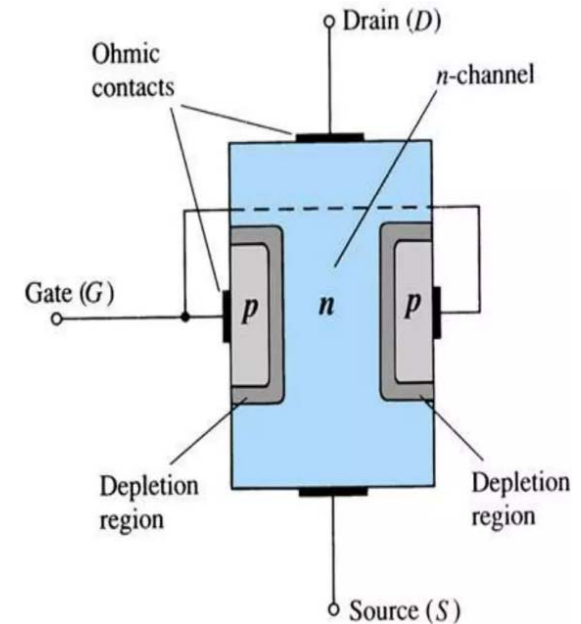
Types of FETs:

- 1) Junction field-effect transistor (JFET).
- 2) Metal-oxide-semiconductor field-effect transistor (MOSFET).
 - i) Depletion type MOSFET.
 - ii) Enhancement type MOSFET.
- 3) Metal-semiconductor field-effect transistor (MESFET).



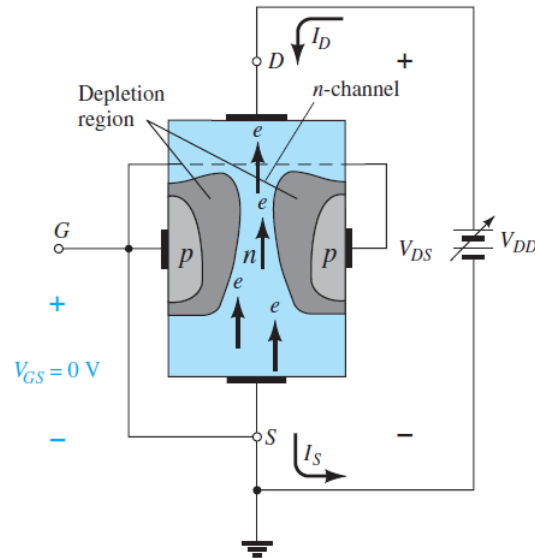
Construction of JFETs

- Source →
through which majority carriers enter into channel.
- Drain →
through which majority carriers leave from channel.
- Gate →
two internally connected heavily doped impurity region.
- Channel →
region between source and drain.
sandwiched between two gates.
- No-bias condition →
two p - n junctions.
depletion region at each junction.

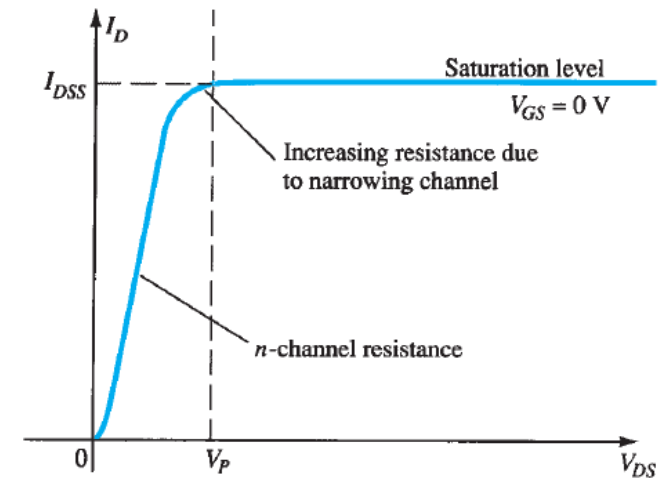
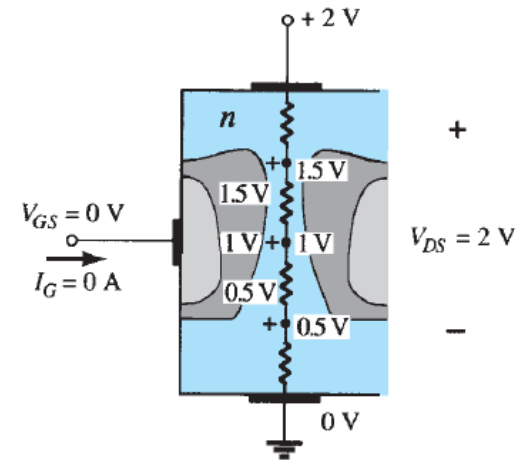
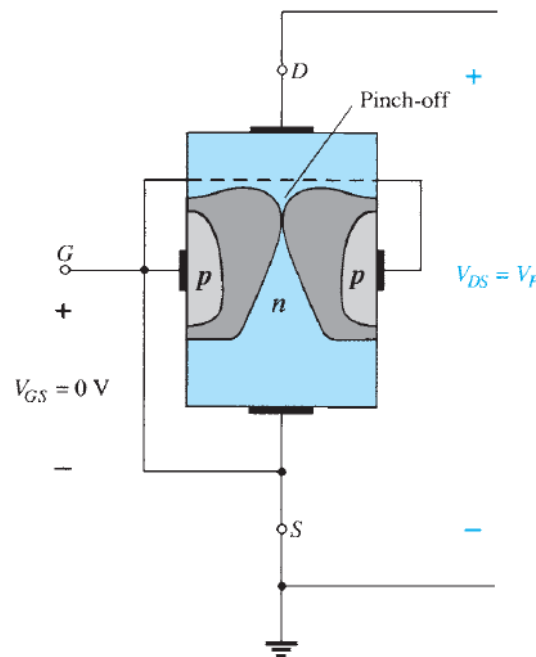


Characteristics of JFETs

$V_{GS} = 0\text{ V}$, $V_{DS} = \text{Some +ve value}$



Depletion region is wider near top of both p -type
Reason for change in width \rightarrow



Characteristics of JFETs

I_D does not drop off at pinch-off \rightarrow

absence of I_D = absence of different potential levels through n -channel.
loss of depletion region distribution.

$V_{DS} > V_P \rightarrow$

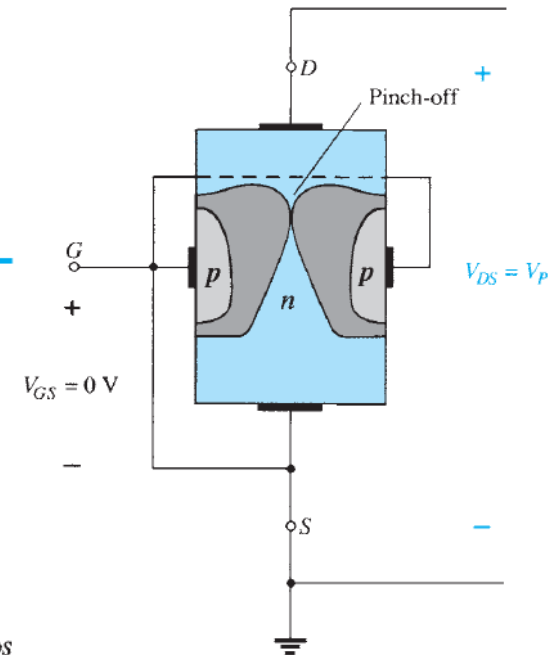
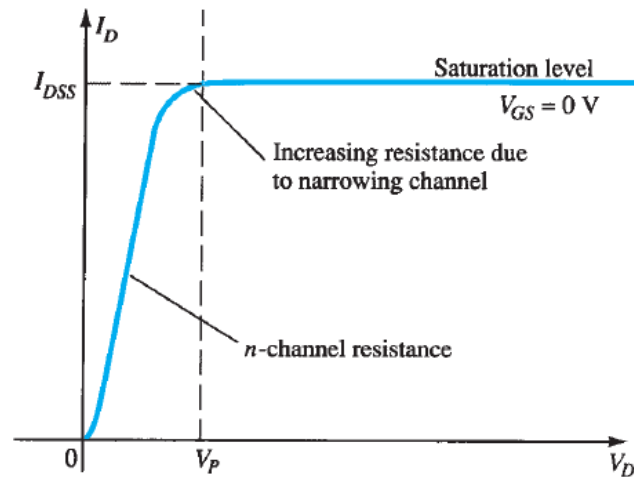
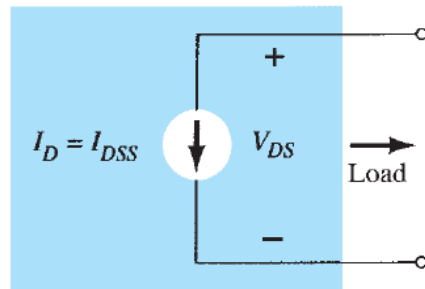
region of close encounter between two depletion regions increases in length.
level of I_D remains same.

JFET = characteristics of current source.

current is fixed at $I_D = I_{DSS}$

I_{DSS} = maximum drain current

Condition = $V_{GS} = 0$ V and $V_{DS} > |V_P|$.



Characteristics of JFETs

$$V_{GS} < 0 \text{ V} \rightarrow$$

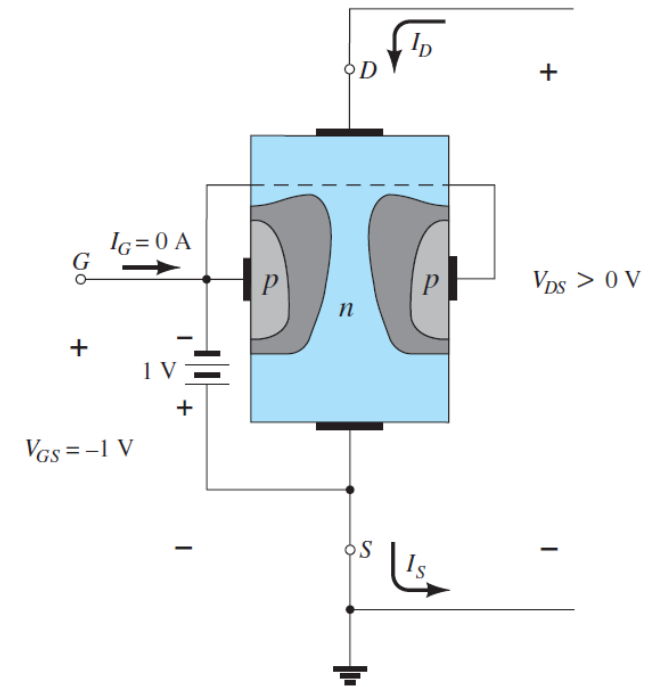
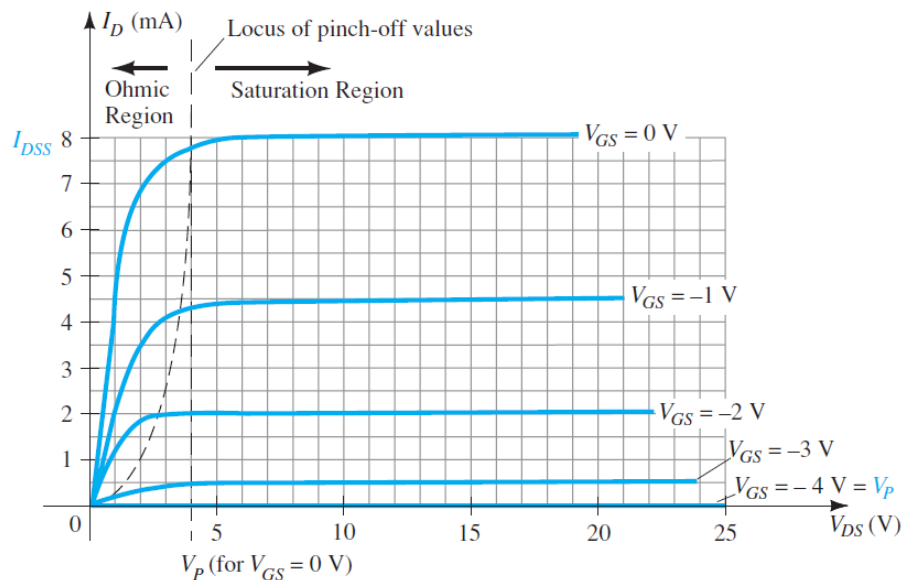
V_{GS} is controlling voltage of JFET.

For *n*-channel, V_{GS} is made more and more -ve.

Effect of applied negative-bias \rightarrow

Establish depletion regions = obtained with $V_{GS} = 0 \text{ V}$ at lower levels of V_{DS} .

Reach saturation level at lower level of V_{DS} .



Characteristics of JFETs

Ohmic or voltage-controlled resistance region →
 JFET is employed as variable resistor.
 resistance is controlled by applied V_{GS} .
 V_{GS} becomes more and more negative =
 resistance level increases.

$$r_d = \frac{r_o}{(1 - V_{GS}/V_P)^2}$$

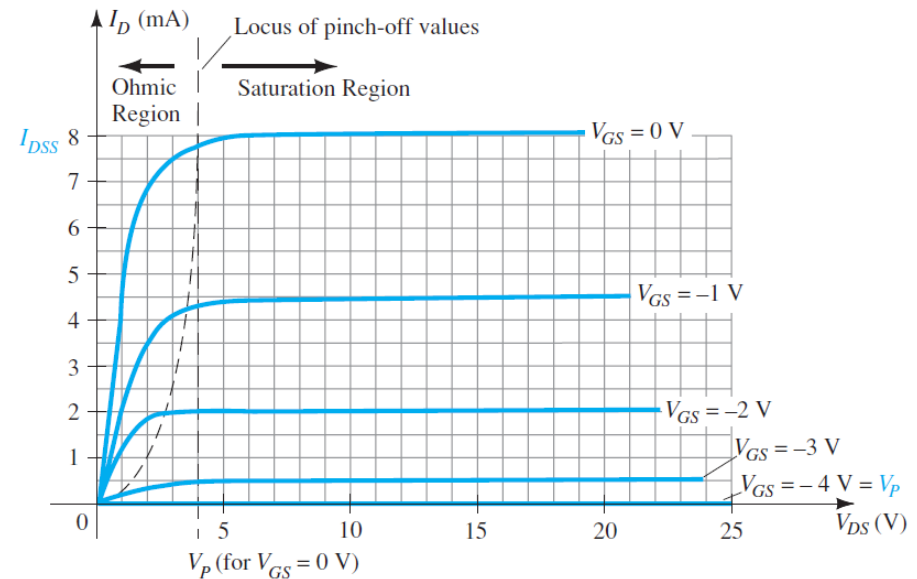
r_o = resistance with $V_{GS} = 0$ V

r_d = resistance at particular level of V_{GS} .

For n -channel JFET →

$r_o = 10 \text{ k}\Omega$ ($V_{GS} = 0$ V, $V_P = -6$ V)

$r_d = 40 \text{ k}\Omega$ at $V_{GS} = -3$ V.



Characteristics of JFETs

Transfer characteristics = plot of I_D versus V_{GS} .

Shockley's equation \rightarrow

$$I_D = I_{DSS} \left(1 - \frac{V_{GS}}{V_P} \right)^2$$

I_{DSS} , V_P = constants.

V_{GS} = control variable.

nonlinear relationship between I_D and V_{GS} ,

curve grows exponentially with decreasing $|V_{GS}|$.

